

L Number	Hits	Search Text	DB	Time stamp
201	61650	electron adj beam or e-beam	USPAT	2004/07/21 17:22
202	148407	electron adj beam or e-beam	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 17:22
203	144149	electron adj beam or e-beam with exposure adj dose	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 17:24
204	144142	electron adj beam or e-beam with exposure adj dose with pattern	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 17:24
205	80	(electron adj beam or e-beam) with exposure adj dose with pattern	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 18:11
206	226	(electron adj beam or e-beam) with exposure adj dose	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 17:24
207	5	(electron adj beam or e-beam) with (smear\$4 adj function or blur\$4 adj function)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 18:17
208	91	(electron adj beam or e-beam) near (smear\$4 or blur\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 18:33
209	24	(pec or proximity adj effect adj compensation) with electron adj beam	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 18:41
210	0	(regularization or regularisation) with (electron adj beam or e-beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 18:51
211	603	(proximity near effect) with (electron adj beam or e-beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 18:51
212	600	(proximity adj effect) with (electron adj beam or e-beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/21 18:51